

10673820\_CLS  
Most Frequently Occurring Classifications of Patents Returned  
From A Search of 10673820 on March 17, 2004

Original Classifications

4 430/5  
3 250/491.1  
2 250/492.3  
2 355/53  
2 427/498  
2 430/296

Cross-Reference Classifications

5 250/492.2  
3 427/407.1  
3 427/496  
3 427/504  
3 427/526  
3 430/942  
2 250/396R  
2 250/492.22  
2 250/492.3  
2 250/505.1  
2 313/309  
2 315/5.31  
2 369/103  
2 369/44.12  
2 369/44.23  
2 427/259  
2 427/264  
2 427/525  
2 427/533  
2 427/552  
2 430/296  
2 430/945  
2 438/933

Combined Classifications

6 250/492.2  
4 250/492.3  
4 430/296  
4 430/5  
3 250/491.1  
3 250/492.22  
3 369/103  
3 369/44.12  
3 427/407.1  
3 427/496

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3 427/504  
3 427/526  
3 430/942  
2 250/396R  
2 250/505.1  
2 313/309  
2 313/336  
2 315/5.31  
2 355/53  
2 369/100  
2 369/44.23  
2 427/259  
2 427/264  
2 427/498  
2 427/525  
2 427/533  
2 427/552  
2 430/945  
2 438/87  
2 438/933

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Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10673820 on March 17, 2004

6	250/492.2	(1 OR, 5 XR)	
	Class 250 :	RADIANT ENERGY	
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL	
	250/492.2	.Irradiation of semiconductor devices	
4	250/492.3	(2 OR, 2 XR)	
	Class 250 :	RADIANT ENERGY	
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL	
	250/492.3	.Ion or electron beam irradiation	
4	430/296	(2 OR, 2 XR)	
	Class 430 :	RADIATION IMAGERY CHEMISTRY: PROCESS,	
		COMPOSITION, OR PRODUCT THEREOF	
	430/269	IMAGING AFFECTING PHYSICAL PROPERTY OF	
		RADIATION SENSITIVE MATERIAL, OR PRODUCING	
NONPLANAR OR			
		PRINTING SURFACE - PROCESS, COMPOSITION, O	
R PRODUCT			
	430/296	.Electron beam imaging	
4	430/5	(4 OR, 0 XR)	
	Class 430 :	RADIATION IMAGERY CHEMISTRY: PROCESS,	
		COMPOSITION, OR PRODUCT THEREOF	
	430/4	RADIATION MODIFYING PRODUCT OR PROCESS OF	
		MAKING	
	430/5	.Radiation mask	
3	250/491.1	(3 OR, 0 XR)	
	Class 250 :	RADIANT ENERGY	
	250/491.1	MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE	
		TO A SOURCE OR DETECTOR	
3	250/492.22	(1 OR, 2 XR)	
	Class 250 :	RADIANT ENERGY	
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL	
	250/492.2	.Irradiation of semiconductor devices	
	250/492.22	..Pattern control	
3	369/103	(1 OR, 2 XR)	
	Class 369 :	DYNAMIC INFORMATION STORAGE OR RETRIEVAL	
	369/99	SPECIFIC DETAIL OF INFORMATION HANDLING PORTIO	
N			
		OF SYSTEM	

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369/100 .Radiation beam modification of or by storage medium

369/103 ..Holographic

3 369/44.12 (1 OR, 2 XR)

Class 369 : DYNAMIC INFORMATION STORAGE OR RETRIEVAL

369/43 WITH SERVO POSITIONING OF TRANSDUCER ASSEMBLY OVER TRACK COMBINED WITH INFORMATION SIGNAL PROCESSING

369/44.11 .Optical servo system

369/44.12 ..Solid state optical element with plural dissimilar optical components (e.g., using I.C. block, etc.)

3 427/407.1 (0 OR, 3 XR)

Class 427 : COATING PROCESSES

427/402 APPLYING SUPERPOSED DIVERSE COATING OR COATING A COATED BASE

427/407.1 .Synthetic resin coating

3 427/496 (0 OR, 3 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR PARTICULATE ENERGY

427/487 .Polymerization of coating utilizing direct application of electrical, magnetic, wave, or particulate energy (i.e., including cross-linking, curing, and hardening of organics)

427/496 ..High energy electromagnetic radiation or high energy particles utilized (e.g., gamma rays, X-rays, atomic particles, i.e., alpha rays, beta rays, electrons, etc.)

3 427/504 (0 OR, 3 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR PARTICULATE ENERGY

427/487 .Polymerization of coating utilizing direct application of electrical, magnetic, wave, or particulate energy (i.e., including cross-linking, curing, and hardening of organics)

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427/496      ..High energy electromagnetic radiation or high energy particles utilized (e.g., gamma rays, X-rays, atomic particles, i.e., alpha rays, beta rays, electrons, etc.)

427/504      ...Nonuniform or patterned coating (e.g., mask printing, etc.)

3 427/526      (0 OR, 3 XR)  
     Class 427 : COATING PROCESSES  
     427/457      DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR PARTICULATE ENERGY  
     427/523      .Ion plating or implantation  
     427/526      ..Nonuniform or patterned ion plating or ion implanting (e.g., mask, etc.)

3 430/942      (0 OR, 3 XR)  
     Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF  
     430/942      ELECTRON BEAM

2 250/396R      (0 OR, 2 XR)  
     Class 250 : RADIANT ENERGY  
     250/396R      WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING

2 250/505.1      (0 OR, 2 XR)  
     Class 250 : RADIANT ENERGY  
     250/505.1      RADIATION CONTROLLING MEANS

2 313/309      (0 OR, 2 XR)  
     Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES  
     313/309      DISCHARGE DEVICES HAVING A MULTIPOINTED OR SERRATED EDGE ELECTRODE

2 313/336      (1 OR, 1 XR)  
     Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES  
     313/326      ELECTRODE AND SHIELD STRUCTURES  
     313/336      .Point source cathodes

2 315/5.31      (0 OR, 2 XR)  
     Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS  
     315/1      CATHODE RAY TUBE CIRCUITS  
     315/3      .Combined cathode ray tube and circuit element structure

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315/4 ..Inductor or distributed parameter-type  
inductive structure

315/5 ...Ray passes in or through a hollow  
distributed parameter device

315/5.29 ....Ray has appreciable transverse electrical  
dimension and/or significant shape

315/5.31 .....Hollow ray

2 355/53 (2 OR, 0 XR)  
Class 355 : PHOTOCOPYING  
355/18 PROJECTION PRINTING AND COPYING CAMERAS  
355/53 .Step and repeat

2 369/100 (1 OR, 1 XR)  
Class 369 : DYNAMIC INFORMATION STORAGE OR RETRIEVAL  
369/99 SPECIFIC DETAIL OF INFORMATION HANDLING PORTIO

N  
OF SYSTEM  
369/100 .Radiation beam modification of or by storage  
medium

2 369/44.23 (0 OR, 2 XR)  
Class 369 : DYNAMIC INFORMATION STORAGE OR RETRIEVAL  
369/43 WITH SERVO POSITIONING OF TRANSDUCER ASSEMBLY  
OVER TRACK COMBINED WITH INFORMATION SIG

NAL PROCESSING  
369/44.11 .Optical servo system  
369/44.14 ..Optical head servo system structure  
369/44.23 ...Structure for shaping beam or causing  
astigmatic condition

2 427/259 (0 OR, 2 XR)  
Class 427 : COATING PROCESSES  
427/256 NONUNIFORM COATING  
427/258 .Applying superposed diverse coatings or  
coating a coated base  
427/259 ..Including a masking coating

2 427/264 (0 OR, 2 XR)  
Class 427 : COATING PROCESSES  
427/256 NONUNIFORM COATING  
427/258 .Applying superposed diverse coatings or  
coating a coated base  
427/261 ..Final coating nonuniform  
427/264 ...Deforming the base or coating or removing a  
portion of the coating

2 427/498 (2 OR, 0 XR)

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Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,  
WAVE, OR PARTICULATE ENERGY

427/487 .Polymerization of coating utilizing direct  
application of electrical, magnetic, wave  
, or particulate  
energy (i.e., including cross-linking, cu  
ring, and  
hardening of organics)

427/496 ..High energy electromagnetic radiation or hig  
h  
energy particles utilized (e.g., gamma ray  
s, X-rays, atomic  
particles, i.e., alpha rays, beta rays, el  
ectrons, etc.)

427/498 ...Immersion, partial immersion, spraying, or  
spin coating utilized (e.g., dipping, etc.)

2 427/525 (0 OR, 2 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,  
WAVE, OR PARTICULATE ENERGY

427/523 .Ion plating or implantation

427/525 ..Organic material present in substrate,  
plating, or implanted layer

2 427/533 (0 OR, 2 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,  
WAVE, OR PARTICULATE ENERGY

427/532 .Pretreatment of substrate or post-treatment o  
f  
coated substrate

427/533 ..Ionized gas utilized (e.g., electrically  
powered source, corona discharge, plasma, g  
low discharge,  
etc.)

2 427/552 (0 OR, 2 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,  
WAVE, OR PARTICULATE ENERGY

427/532 .Pretreatment of substrate or post-treatment o  
f  
coated substrate

427/551 ..High energy electromagnetic radiation or hig  
h

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energy particles utilized (e.g., gamma ray  
, X-ray, atomic  
particle, i.e., alpha ray, beta ray, high  
energy electron,  
etc.)  
427/552 ...Nonuniform or patterned coating

2 430/945 (0 OR, 2 XR)  
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
COMPOSITION, OR PRODUCT THEREOF  
430/945 LASER BEAM

2 438/87 (1 OR, 1 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
438/51 ..Packaging (e.g., with mounting,  
encapsulating, etc.) or treatment of pac  
kaged  
semiconductor  
438/57 .Responsive to electromagnetic radiation  
438/87 ..Graded composition

2 438/933 (0 OR, 2 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
438/933 GERMANIUM OR SILICON OR GE-SI ON III-V